



NOTES:

1. MATERIAL: UVFS
2. COATING (S1) : HIGH ENERGY LASER LINE COATING
 $R_s, R_p > 99\% @ 780 \text{ nm}, 0^\circ - 45^\circ \text{ AOI}$
3. CLEAR APERTURE (S1, S2) : $> 90\%$ (CA)
4. SURFACE QUALITY (S1, S2) : 20/10 (S/D)
5. SURFACE FLATNESS (S1, S2) : $\lambda/6 @ 633 \text{ nm}$
6. PARALLELISM (S1, S2) : $< 3 \text{ arcmin}$
7. CHAMFER: $< 0.2 \text{ mm}, 45^\circ$
8. BACK SURFACE (S2) : POLISH

DRAWING PROJECTION			LBTEK			
	NAME	DATE				
DRAWN	YZENG	Apr./25th/24	HIGH ENERGY LASER LINE MIRROR $\text{Ø} 30 \text{ mm} \times 6 \text{ mm}, 780 \text{ nm}$			
APPROVAL	WCHENG	Apr./25th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	9.34 g	2:1	A